

L Number	Hits	Search Text	DB	Time stamp
1	8	Epshteyn	US-PGPUB	2003/10/30 09:33
-	2410	(cmp or polishing or polish or planrize or planarizing) and (buff or buffing)	USPAT	2003/10/29 13:14
-	552	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TN or Ti)	USPAT	2003/01/15 11:39
-	723	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti)	USPAT	2003/01/15 15:59
-	32	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (end\$point or (end adj point))	USPAT	2003/01/15 15:08
-	528	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (condition or conditioning or conditioned)	USPAT	2003/01/15 16:00
-	503	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (condition or conditioning or conditioned) not (((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (end\$point or (end adj point)))	USPAT	2003/01/15 16:00
-	84	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (conditioning or conditioned)	USPAT	2003/01/15 16:00
-	75	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (conditioning or conditioned) not (((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (end\$point or (end adj point)))	USPAT	2003/01/15 16:00
-	2410	(cmp or polishing or polish or planrize or planarizing) and (buff or buffing)	USPAT	2003/01/16 14:38
-	723	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti)	USPAT	2003/01/16 14:39
-	84	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (conditioning or conditioned)	USPAT	2003/01/16 15:43
-	113	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (infra\$red or (infra adj red))	USPAT	2003/01/16 15:44
-	66	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (infra\$red or (infra adj red)) and current	USPAT	2003/01/16 15:58
-	18	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier or liner or Ta or TiN or Ti) and (end\$point or (end adj point)) and current	USPAT	2003/01/16 16:01
-	10	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and ((end\$point or (end adj point)) with current)	USPAT	2003/01/16 16:03

-	2611	(cmp or polishing or polish or planrize or planarizing) and (buff or buffing)	USPAT	2003/10/29 14:40
-	321	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and barrier	USPAT	2003/10/29 13:25
-	37	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier with (buff or buffing))	USPAT	2003/10/29 13:25
-	35	((cmp or polishing or polish or planrize or planarizing) and (buff or buffing)) and (barrier with (buff or buffing)) and @ay<=2001	USPAT	2003/10/29 14:29
-	1	5897426.pn.	USPAT	2003/10/29 14:40
-	1539	(cmp or polishing or polish or planrize or planarizing) and (end\$1point)	USPAT	2003/10/29 14:40
-	14	((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and infra	USPAT	2003/10/29 14:52
-	133	((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and (infra or infra\$1red or IR)	USPAT	2003/10/29 14:53
-	119	((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and (infra or infra\$1red or IR) not ((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and infra	USPAT	2003/10/29 14:54
-	107	((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and (infra or infra\$1red or IR) not ((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and infra	USPAT	2003/10/29 14:55
-	48	((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and (infra or infra\$1red or IR) not ((cmp or polishing or polish or planrize or planarizing) and (end\$1point)) and laser and infra	USPAT	2003/10/29 15:37
-	30	Politex adj Supreme	USPAT	2003/10/29 15:46
-	750	(buff or buffing) same (condition or conditioning)	USPAT	2003/10/29 15:47
-	379	(buff or buffing) with (condition or conditioning)	USPAT	2003/10/29 16:28
-	42	((buff or buffing) with (condition or conditioning)) and semiconductor	USPAT	2003/10/29 15:47
-	38	((buff or buffing) with (condition or conditioning)) and semiconductor) and @ay<=2000	USPAT	2003/10/29 15:51
-	1	5738574.pn.	USPAT	2003/10/29 15:51
-	1	5738574.pn. and (buff or buffing)	USPAT	2003/10/29 15:52
-	1	(5738574.pn. and (buff or buffing)) and (condition or conditioning or conditioned)	USPAT	2003/10/29 16:15
-	8	Epshteyn	US-PGPUB	2003/10/30 09:33
-	22	((buff or buffing) near pad) with (condition or conditioning)	USPAT	2003/10/29 16:28
-	26	((buff or buffing) near (pad or cloth)) with (condition or conditioning)	USPAT	2003/10/29 16:28
-	25	((buff or buffing) near (pad or cloth)) with (condition or conditioning) and @ay<=2000	USPAT	2003/10/29 16:32
-	0	(buff or buffing) with (politex adj supreme)	USPAT	2003/10/29 16:33

-	30	politex adj supreme	USPAT	2003/10/29 16:33
-	28	(politex adj supreme) and (buff or buffing or pad)	USPAT	2003/10/29 16:33
-	4	(politex adj supreme) and (buff or buffing)	USPAT	2003/10/29 16:33